



#116  
7/16/02  
PATENT

Customer No. 22,852  
Attorney Docket No. 08038.0044

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
Mitsuaki KOMINO et al. ) Group Art Unit: 1763  
Serial No.: 09/667,777 ) Examiner: R. Zervigon  
Filed: September 22, 2000 )  
For: ELECTRODE, SUSCEPTOR, PLASMA )  
PROCESSING APPARATUS AND )  
METHOD OF MAKING THE )  
ELECTRODE AND THE SUSCEPTOR )

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action dated December 26, 2001, the period for reply having been extended for three months by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE SPECIFICATION:

Please amend the paragraph beginning at line 36 of page 10 and ending at line 2 of page 11 as follows:

Upon application of the plasma generation high frequency voltage to the upper electrode 70, the film forming gases are converted into a plasma, activated, and reacted to form a film of, for example, SiOF on the surface of the waver.

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